Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S13 9	0	(sige or silicon near2 germanium) near16 laser and 117/3.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/23 12:12
S14 0	266	(sige or silicon near2 germanium) near16 laser and (crystal\$6 or recrystal\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/23 12:13
S14 2	44	(sige or silicon near2 germanium) near16 laser same (crystal\$6 or recrystal\$6) same (anneal\$5 or heat near2 treat\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/23 13:08
S14 1	109	(sige or silicon near2 germanium) near16 laser same (crystal\$6 or recrystal\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/23 13:08
S14 4	40	(sige or silicon near2 germanium) near16 (laser or heat near2 treat\$5) and etch\$6 near5 selectiv\$6 near16 (sige or silicon near2 germanium)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:48
S14 3	69	(sige or silicon near2 germanium) near16 (laser or heat near2 treat\$5) and pattern\$6 near16 (sige or silicon near2 germanium)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:48
S14 5	184	(shunpei.in. near2 yamazaki.in.) and laser near3 (crystal\$4 or crystalliz\$4 or anneal\$4) same ((silicon or si) and (ge or germanium)) and pattern\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:50
S84	85	(shunpei.in. near2 yamazaki.in.) and laser near3 (crystal\$4 or crystalliz\$4 or anneal\$4) same ((silicon or si) and (ge or germanium)) same amorphous	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:50
S14 9	3	(shunpei.in. near2 yamazaki.in.) and laser near3 (crystal\$4 or crystalliz\$4 or anneal\$4) same ((silicon or si) near2(ge or germanium)) near10 amorphous same pattern\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:51

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S14 8	64	(shunpei.in. near2 yamazaki.in.) and laser near3 (crystal\$4 or crystalliz\$4 or anneal\$4) same ((silicon or si) near5 (ge or germanium)) same pattern\$6 same amorphous	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:51
S14 7	65	(shunpei.in. near2 yamazaki.in.) and laser near3 (crystal\$4 or crystalliz\$4 or anneal\$4) same ((silicon or si) and (ge or germanium)) same pattern\$6 same amorphous	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:51
S14 6	65	(shunpei.in. near2 yamazaki.in.) and laser near3 (crystal\$4 or crystalliz\$4 or anneal\$4) same ((silicon or si) and (ge or germanium)) same pattern\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:51
S12 9	7192	(shunpei near2 yamazaki or toru near2 mitsuki or kenji near2 kasahara or tamae near2 takano or takeshi near2 shichi or chiho near2 kokubo).in. or semiconductor near2 energy near2 laboratory.as.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:52
S15 0	3272	((shunpei near2 yamazaki or toru near2 mitsuki or kenji near2 kasahara or tamae near2 takano or takeshi near2 shichi or chiho near2 kokubo). in. or semiconductor near2 energy near2 laboratory.as.) and laser near16 (crystal\$6 anneal\$6 or recrystal\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:53
S15 2	182	((shunpei near2 yamazaki or toru near2 mitsuki or kenji near2 kasahara or tamae near2 takano or takeshi near2 shichi or chiho near2 kokubo). in. or semiconductor near2 energy near2 laboratory.as.) and laser near16 (crystal\$6 anneal\$6 or recrystal\$6) same (sige or silicon near2 germanium) same pattern\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:54
S15 1	490	((shunpei near2 yamazaki or toru near2 mitsuki or kenji near2 kasahara or tamae near2 takano or takeshi near2 shichi or chiho near2 kokubo). in. or semiconductor near2 energy near2 laboratory.as.) and laser near16 (crystal\$6 anneal\$6 or recrystal\$6) same (sige or silicon near2 germanium)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:54
S15 5	156	pattern\$6 near15 (sige or silicon near2 germanium) near16 (device or tft)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:59

S15 4	2	"20020043660".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 17:59
S15 6	8	pattern\$6 near15 (sige or silicon near2 germanium) near16 (device or tft) and @py<"2000"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 18:01
S15 8	6	pattern\$6 near15 (sige or silicon near2 germanium) and (silicon near2 germanium or sige) near10 (laser) and @py<"2002"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 18:02
S15 7	1	pattern\$6 near15 (sige or silicon near2 germanium) near16 (laser) and @py<"2002"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 18:02
S15 9	48	(US-20020019101-\$ or US-20020043660-\$ or US-20020113268-\$ or US-20010002324-\$).did. or (US-6350311-\$ or US-4766091-\$ or US-6130981-\$ or US-5834071-\$ or US-4309225-\$ or US-5766989-\$ or US-4975387-\$ or US-6261881-\$ or US-5272365-\$ or US-5712191-\$ or US-4705734-\$ or US-6066547-\$ or US-6277679-\$ or US-6461945-\$ or US-5578520-\$ or US-5893949-\$ or US-6495404-\$ or US-5726487-\$ or US-6495404-\$ or US-5726487-\$ or US-6482684-\$ or US-5821135-\$ or US-6482684-\$ or US-5821135-\$ or US-6225197-\$ or US-5821158-\$ or US-6225197-\$ or US-5767003-\$).did. or (US-6423585-\$ or US-5753541-\$ or US-6346716-\$ or US-6118151-\$ or US-6346716-\$ or US-6118151-\$ or US-5922125-\$ or US-5847419-\$ or US-5923966-\$ or US-5847419-\$ or US-5923966-\$ or US-5512772-\$).did. or (JP-59129859-\$ or JP-04168769-\$ or JP-01053408-\$ or JP-04168769-\$ or JP-03284882-\$ or JP-2002093705-\$ or JP-2000003875-\$).did. or (JP-11087242-\$).did.	US-PGPUB; USPAT; JPO; DERWENT	OR	ON	2006/02/26 18:25
S16 0	32	S159 and (pattern\$5 or selectiv\$6 near2 etch\$6)	US-PGPUB; USPAT; JPO; DERWENT	OR	ON	2006/02/26 18:27

S16 6	5	"0962963"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/02/26 19:27
S16 5	5	"0962963"	US-PGPUB; USPAT; JPO; DERWENT	OR	ON	2006/02/26 19:27
S16 4	82	"962963"	US-PGPUB; USPAT; JPO; DERWENT	OR	ON	2006/02/26 19:27
S16 3	1	"0962963".pn.	US-PGPUB; USPAT; JPO; DERWENT	OR	ON	2006/02/26 19:27
S16 2	3	"962963".pn.	US-PGPUB; USPAT; JPO; DERWENT	OR	ON	2006/02/26 19:27
S16 1	10	S159 and (pattern\$5 or selectiv\$6 near2 etch\$6) same (sige or silicon near2 germanium)	US-PGPUB; USPAT; JPO; DERWENT	OR	ON	2006/02/26 19:27
S16 9	0	"6270573".pn. and homoepitax46	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/02/26 19:28
S16 8	7	"6270573"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/02/26 19:28
S16 7	83	"962963"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/02/26 19:28
S17 0	1	"6270573".pn. and homoepitax\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/02/26 19:29
S17 1	14	(etch\$6 or pattern\$6) near17 (sige or silicon near2 germanium) near16 laser	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 13:37

S17 2	852	(etch\$6 or pattern\$6) near17 laser near5 (anneal\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT;	OR	ON	2006/03/01 13:44
S17 3	165	(etch\$6 or pattern\$6) near17 laser near5 (anneal\$5) same (tft or thin near2 film near2 transist\$5)	IBM_TDB US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 13:46
S17 4	4	"9931719"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 14:00
S17 6	9	"6077731".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 14:01
S17 5	2	"6063654".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 14:01
L4	29	laser near2 crystal\$6 near10 (si or silicon) near2 excimer and @py<"2000"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/05 20:20
L3	247	laser near2 crystal\$6 near10 (si or silicon) near2 excimer and 2py<"200"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/05 20:20
L2	247	laser near2 crystal\$6 near10 (si or silicon) near2 excimer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/05 20:20
L1	2102	laser near2 crystal\$6 near10 (si or silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/05 20:20

S15 3	39	((shunpei near2 yamazaki or toru near2 mitsuki or kenji near2 kasahara or tamae near2 takano or takeshi near2 shichi or chiho near2 kokubo). in. or semiconductor near2 energy near2 laboratory.as.) and laser near16 (crystal\$6 anneal\$6 or recrystal\$6) same (sige or silicon near2 germanium) same pattern\$6 and @py<"2003"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/05 20:51
L5	491	((shunpei near2 yamazaki or toru near2 mitsuki or kenji near2 kasahara or tamae near2 takano or takeshi near2 shichi or chiho near2 kokubo). in. or semiconductor near2 energy near2 laboratory.as.) and laser near16 (crystal\$6 anneal\$6 or recrystal\$6) same (sige or silicon near2 germanium)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/05 20:51

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